

## WHAT IS CLAIMED IS:

A transparent laminate comprising:

a transparent substrate;

three or four combination thin-film layers successively

laminated on a surface of said transparent substrate, each of said thin-film layers consisting of a high-refractive-index transparent thin film and a silver transparent conductive thin film; and

another high-refractive-index transparent thin film

formed on a surface of said combination thin-film layer,

wherein a standard deviation of visible light

transmittance in a wave range of from 450 to 650 nm is not larger

than 5%.

- 2. A transparent laminate according to claim 1, wherein each of said silver transparent conductive thin films has a thickness in a range of from 5 to 20 nm, each of the high-refractive-index transparent thin film located on the surface of said transparent substrate and the
- high-refractive-index transparent thin film located in an outermost layer has a thickness in a range of 20 to 50 nm, and each of the other high-refractive-index transparent thin films located in an intermediate region between said high-refractive-index transparent thin film located on the surface of said transparent substrate and said



high-refractive-index transparent thin film located as the outermost layer has a thickness in a range of 40 to 100 nm.

3. A transparent laminate according to claim 1, wherein each of said silver transparent conductive thin films has an approximately constant thickness in a range of from 5 to 20 nm, each of the high-refractive-index transparent thin film located on the sunface of said transparent substrate and the high-refractive-index transparent thin film located in an outermost layer has a thickness  $(5/2) \times (1\pm0.15)$  times as large as the thickness of each of said silver transparent conductive thin films, and each of the other high-refractive-index transparent thin films located in an intermediate region between said high-refractive-index transparent thin film located on the surface of said transparent substrate and said high-refractive-index transparent thin film located as the outermost layer has a thickness  $5 \times (1 \pm 0.15)$  times as large as the thickness of each of said silver transparent conductive thin films.

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4. A transparent laminate according to claim 1, further comprising a low-refractive index transparent thin film formed on said surface of said transparent substrate, said low-refractive-index transparent thin film having a refractive index  $n_L$  in a range of from 1.3 to 1.6 and having a thickness

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of 550 nm $\times$  (1/4n<sub>L</sub>)  $\times$  (1±0.15).

- 5. A transparent laminate according to claim 4, further comprising a low-refractive-index transparent thin film formed on a surface of said high-refractive-index transparent thin film located as the outermost layer, said low-refractive-index transparent thin film having a refractive index  $n_L$  in a range of from 1.3 to 1.6 and having a thickness of 550 nm $\times$  (1/2 $n_L$ )  $\times$  (1±0.15).
- further comprising any one of an anti-reflection film, an anti-mirroring film and a low-reflection anti-mirroring film stuck onto said surface of said high-refractive-index transparent thin film located as the outermost layer, through a transparent adhesive layer.
  - 7. A plasma display panel filter comprising a transparent laminate according to claim 1.
  - 8. A plasma display panel filter comprising a transparent laminate according to claim 2.
- 9. A plasma display panel filter comprising a 25 transparent laminate according to claim 3.



- 10. A plasma display panel filter comprising a transparent laminate according to claim 4
- 11. A plasma display panel filter comprising a transparent laminate according to claim 5.
  - 12. A plasma display panel filter comprising a transparent laminate according to claim 6.

13. A method for producing a transparent laminate comprising steps of:

preparing a transparent substrate;
depositing a high-refractive-index transparent thin film

depositing a silver transparent conductive thin film by a vacuum dry process;

repeating said steps for depositing the high-refractive-index transparent thin film and the silver transparent conductive thin film three or four times to thereby form three or four combination thin-film layers of the high-refractive-index transparent thin film and the silver transparent conductive thin film successively laminated on a surface of said transparent substrate; and

depositing another high-refractive-index transparent thin film on a surface of said combination thin-film layer by

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by a vacuum dry process;



the vacuum dry process,

wherein, when said silver transparent conductive thin films are deposited by the vacuum dry process, temperature T (K) of said transparent substrate at the time of the deposition of said films is set to be in a range  $340 \le T \le 410$ .

14. A method for producing a transparent laminate comprising steps of:

preparing a transparent substrate;

depositing a high-refractive-index transparent thin film

by a vacuum dry process;

depositing a silver transparent conductive thin film by a vacuum dry process;

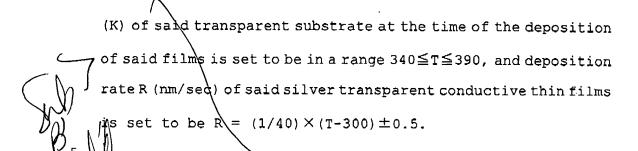
repeating said steps for forming the

high-refractive-index transparent thin film and the silver transparent conductive thin film three or four times to thereby form three or four combination thin-film layers of the high-refractive-index transparent thin film and the silver transparent conductive thin film successively laminated on a surface of said transparent substrate; and

depositing another high-refractive-index transparent thin film on a surface of said combination thin-film layer by the vacuum dry process,

wherein, when said silver transparent conductive thin films are deposited by the vacuum dry process, temperature T





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